Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently Amended) A pattern writing system comprising:

a substrate,

a pattern projecting apparatus using light control elements arranged two-dimensionally, ~~and~~

a microlens array to thereby project onto said substrate a pattern in the form of an aggregate of a large number of spots, and

means for relatively moving said substrate with respect to said pattern projecting apparatus,

wherein ~~characterized in that~~ pattern writing is performed **[[**so**]]** on said substrate such that said substrate is moved obliquely with respect to an array of said large number of spots by said means for relatively moving said substrate, thereby forming the pattern projected, ~~whereby~~ and

wherein some of the spots included in said patterns caused by irradiation at different times overlap with each other at the same position on said substrate so as to realize a level of gradations determined by overlapped times of the spots.

2. (Currently Amended) A pattern writing system according to claim 1, ~~characterized in that~~ wherein said spots each have a polygonal shape.

3. (Currently Amended) A pattern writing system according to claim 1, ~~characterized in that~~ wherein an intensity of irradiation of each spot has an intermediate gradation by one-time irradiation and a required intensity is achieved when the spots are irradiated to overlap with each other a predetermined number of times on the same position on said substrate.

4. (Currently Amended) A pattern writing method for projecting an aggregate pattern of spots arranged in a matrix onto a substrate by relatively moving one of said

aggregate pattern of the spots and said substrate in a predetermined moving direction, said pattern writing method ~~characterized by~~ comprising the steps of:

rendering rows or columns of said aggregate pattern of the spots into an oblique state with respect to the predetermined moving direction; and[[;]]

performing pattern writing by moving said one of said aggregate pattern of the spots and said substrate in said predetermined moving direction, with the oblique state kept intact so as to realize a level of gradations determined by overlapped times of the spots.

5. (Currently Amended) A pattern writing method according to claim 4, ~~characterized in that~~ wherein the spots forming said aggregate pattern of the spots are projected to the same positions on said substrate a plurality of times during movement of said substrate in said predetermined moving direction.

6. (Currently Amended) A pattern writing method according to claim 4, ~~characterized in that~~ wherein the spots projected to the same positions on said substrate the plurality of times are provided by light control elements that are ON/OFF controlled.

7. - 9. (Canceled).

10. (Currently Amended) A pattern writing system ~~characterized by~~ comprising:

a mirror device including micromirrors arranged two-dimensionally,

a light source for supplying exposure light to said mirror device,

a substrate for mask pattern writing,

a moving mechanism for moving said substrate in X- and Y-directions,

means for directly projecting or reduction-projecting projection patterns output from said mirror device onto said substrate, and

control means for overlapping said projection patterns a plurality of times over the substantially whole surface of a pattern projection area on said substrate to thereby perform exposure,

a plurality of said wavelength-conversion solid-state lasers,

a plurality of said mirror devices, and

means for averaging output lights of at least two of said plurality of wavelength-conversion solid-state lasers and supplying the average light to said mirror devices, respectively,

wherein a wavelength-conversion solid-state laser or a microwave-excited excimer laser is used as said light source, and

wherein said means for averaging said output lights and supplying the average light to said mirror device/devices comprises a polarization beam splitter.

11. (Canceled).

12. (Currently Amended) A pattern writing system according to claim 10, ~~characterized by using the~~ wherein a second harmonic of a solid-state laser or a copper vapor laser is used as said light source, and ~~further~~ the system further comprising a wavelength conversion element for converting a wavelength of said projection light.

13. – 23. (Canceled).

24. (Currently Amended) A pattern writing system including a pulse laser light generating portion and two-dimensionally arranged micromirrors and reduction-projecting said micromirrors onto a substrate, said pattern writing system ~~characterized by~~ comprising:

means for generating pulse laser light; ~~and~~

means for performing pattern transfer while overlapping, in both of two perpendicular moving directions on said substrate, projection patterns of said two-dimensionally arranged micromirrors, each projected onto said substrate by one-time pulse laser light; and

a pinhole plate that can divide, into a large number of fine light beams, the pulse laser light from the pulse light source applied to a mirror device including said micromirrors,

wherein said pinhole plate has a first Peltier element provided on one side of a first surface and a second Peltier element provided on another side of the first surface opposite the one side.

25 – 29. (Canceled).

30. (New) A pattern writing system according to claim 1, wherein said spots each have an octagonal or hexagonal shape.

31. (New) A pattern writing method according to claim 4, wherein said spots each have an octagonal or hexagonal shape.